

PFAS-Free Negative ArF Immersion Resist

Overview of FUJIFILM technology / product

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FUJIFILM Develops PFAS-Free Negative ArF immersion Resist

Demonstrating High Yield in Metal Wiring Processes in Collaboration with "imec"

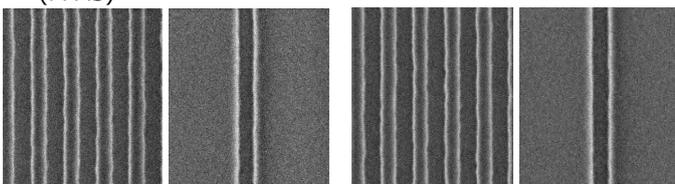
- A negative-type ArF immersion resist (topcoat-free) without containing PFAS, which has the potential environmental and ecological risks.
- Demonstrated the good performance in 28nm generation with IMEC.

Conventional resist (PFAS)

POR

New PFAS-free resist

New



imec

CD 41nm/Pitch 90nm, CD 41nm/Isolated trench.

PFAS-free ArFi resist performance

- Immersion compatibility 😊
- Lithography performance 😊
- Electrical performance 😊

Roadmap

Platform	Development	2024	2025	2026	2027	2028+
ArF/ArFi	Material design Specific customization	Collaborate with consortia		Gen.1		
		Gen.2				

Collaboration required



Not only resist supplier effort but also strong cooperation with partner companies and customers is essential for PFAS replacement to reduce environment impact.